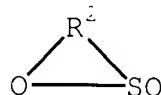


or

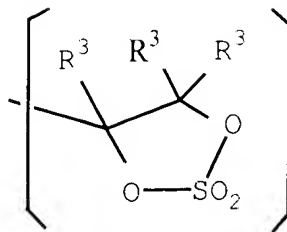


where R^1 and R^2 are, respectively, monovalent and divalent hydrocarbon groups which may be optionally substituted with halogen, NO_2 , oxo ($=O$), CN, alkoxy, hydroxy, acyloxy or SO_2 or interrupted by one or more ether oxygen atoms.

The sulfur-containing compounds are suitably employed at levels of about 0.1-10% by weight of the inventive composition.

More specifically, the thermal resistance conferring compound used in the inventive compositions, include by way of example, acyclic and cyclic sulfates, such as diphenyl sulfate, dibutyl sulfate; and compounds, such as 1,3,2-dioxathiolene-4-ethyl-2,2-dioxide and the di(cyclic

sulfate) of 1,2,7,8-octane tetraol which have one or more groups of the formula:



where R^3 is independently H, alkyl or aryl; anhydrosulfites, such as α -hydroxyisobutyric acid anhydrosulfite; sulfoxides such as dibutylsulfoxide, di- α , α' -phenylethylsulfoxide and α -methylthioxo- δ -butyrolactone; sulfites such as glycol sulfite, dimethyl sulfite, diethyl sulfite and o-phenylene sulfite; sulfonates, such as ethyl methanesulfonate, ethyl trifluoromethane sulfonate, methyl p-toluenesulfonate, n-butyl p-toluenesulfonate, benzyl p-toluenesulfonate, α -methylbenzyl p-toluenesulfonate, α , α -dimethylbenzyl p-toluenesulfonate and the diethyl ester of acetone disulfonic acid; and sulfinates such as methyl-p-toluenesulfonate.

These compounds are usefully employed at levels in the range of about 0.1%-10% by weight of the inventive composition, preferably at least 0.5% and more typically about 0.75%-5% by weight of the inventive composition.